CLAIMS

[Claim 1]

A remover composition for ruthenium which remains on a substrate, wherein

the pH at 25 °C is equal to or above 8, and the composition comprises 1.0 to 2.0 weight % of one or more pH buffering ingredient(s) and periodic acid or a salt thereof.

[Claim 2]

The remover composition according to Claim 1, wherein the pH of the composition at 25 °C is equal to or above 8 and below 11.

[Claim 3]

The remover composition according to Claim 1 or 2, wherein the pH buffering ingredient(s) is(are) one or more selected from the group consisting of boric acid, borate, phosphoric acid, phosphate and bicarbonate.

[Claim 4]

The remover composition according to any one of Claims 1-3, wherein the periodic acid or a salt thereof is one or more selected from the group consisting of ortho-periodic acid, sodium ortho-periodate, meta-periodic acid and sodium meta-periodate.

[Claim 5]

The remover composition according to any one of Claims 1 to 4, comprising from 1.0 to 10.0 weight % of the periodic acid or a salt thereof.

[Claim 6]

The remover composition according to any one of Claims 1 to 5, wherein the remover composition is an aqueous solution.

[Claim 7]

A method of removing ruthenium which remains on a substrate using the remover composition according to any one of Claims 1 to 6.

[Claim 8]

A method of removing ruthenium which remains on a substrate while suppressing the generation of ruthenium tetroxide using a remover composition comprising 1.0 to 2.0 weight % of one or more pH buffering ingredient(s) and the periodic acid or a salt thereof and having pH equal to or above 8 at 25 °C.